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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **TANAKA, et al.**

Group Art Unit: **Unassigned**

Serial No.: **10/091,325**

Examiner: **Unassigned**

Filed: **March 6, 2002**

For. **METHOD AND DEVICE FOR EXPOSURE CONTROL, METHOD AND DEVICE FOR EXPOSURE, AND METHOD OF MANUFACTURE OF DEVICE SYSTEM**

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Date: June 6, 2002

Sir:

Prior to examination on the merits, please amend the above-captioned patent application as follows:

**IN THE CLAIMS:**

Cancel claims 1-61.

Add the following new claims 62-84:

62. (New) An exposure method for transferring a pattern formed on a mask onto a substrate through an optical system, comprising the steps of:

obtaining information relating to a variation in intensity of illumination light on an exposure region on the substrate, the variation in intensity of illumination light being caused by a variation in transmittance of the optical system;

computing information relating to a distribution of illuminance in the exposure region on the substrate;